



Ji Hyun Kim is a foreign attorney at Lee International IP & Law. She advises clients on a variety of issues related to general intellectual property matters including prosecution, litigation, and licensing.

Prior to joining Lee International IP & Law, Ms. Kim worked at Kim & Chang as a foreign attorney and during her stay in the U. S., she accumulated patent-related experiences by working at various leading law firms in Virginia such as Birch, Stewart, Kolasch & Birch, LLP.

Ms. Kim is a graduate of Johns Hopkins University (B.S., Electrical Engineering, Computer Science, and Computer Engineering, 2003) and earned the juris doctor degree at St. John University School of Law in 2009.

Ms. Kim is fluent in English and Korean and has working knowledge of Chinese and Japanese.

Practice Area

- Intellectual Property
- IP litigation and Transaction

Experience

- Lee International IP & Law (2019-Present)
- Kim & Chang (2012-2019)
- Birch, Stewart, Kolasch & Birch, LLP (2010-2011)

Education

- St. John University, School of Law (J.D., 2009)
- Johns Hopkins University (B.S., Electrical Engineering, Computer Science, and Computer Engineering, 2003)

Qualifications

- Admitted to the bar, New York (2010)

Membership

- New York State Bar Association (NYSBA)
- American Bar Association (ABA)

Publications / Presentations

- International Comparative Legal Guides: Trade Marks (2024, 2025)

Awards & Recognition

- International Comparative Legal Guides: Trade Marks - Korea Chapter (2024-2026)

Etc

- Languages : English, Korean, Chinese, French

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